

Ultrafast dynamics of hot carriers in bulk semiconductors and in accumulation layer: energy loss rate and screening effects.

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Collaborations

Ecole Polytechnique, LSI:

N. Vast,

R. Sen (post-doc)

L. Perfetti (ARPES, 2PPE)



Osaka, Japan:

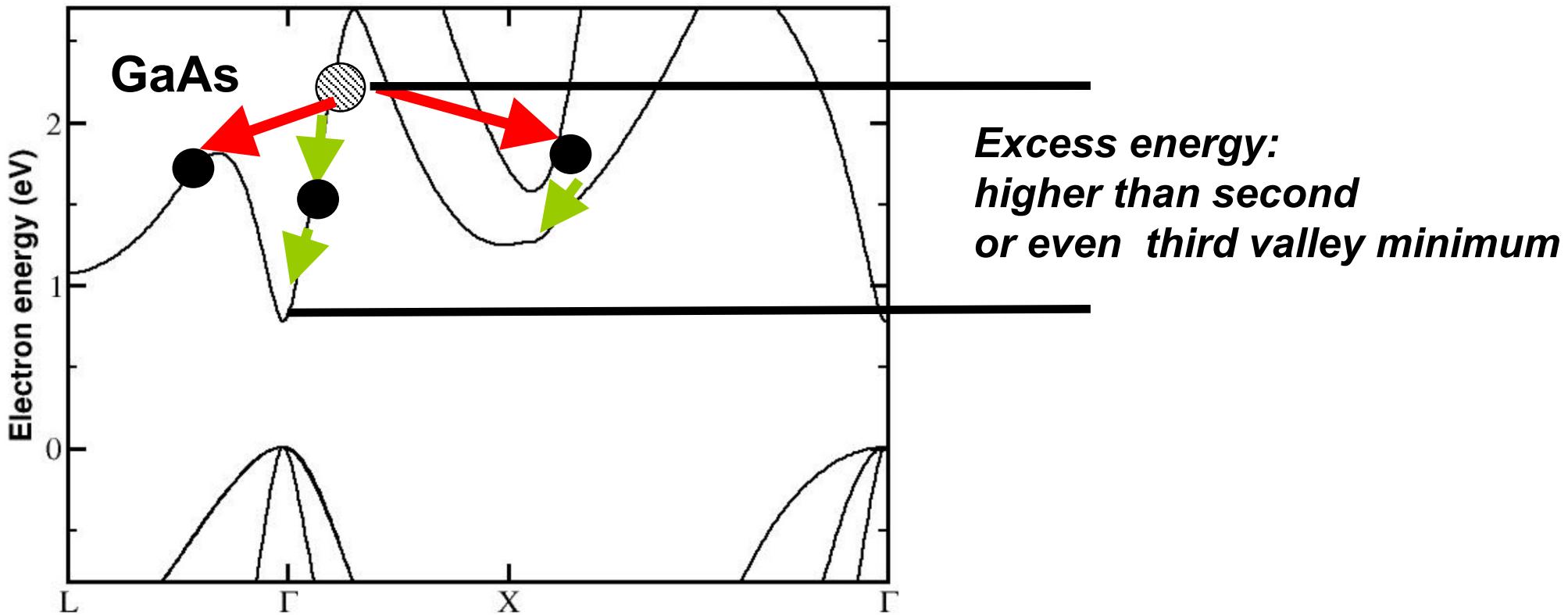
K. Tanimura (ARPES, 2PPE)



Outline

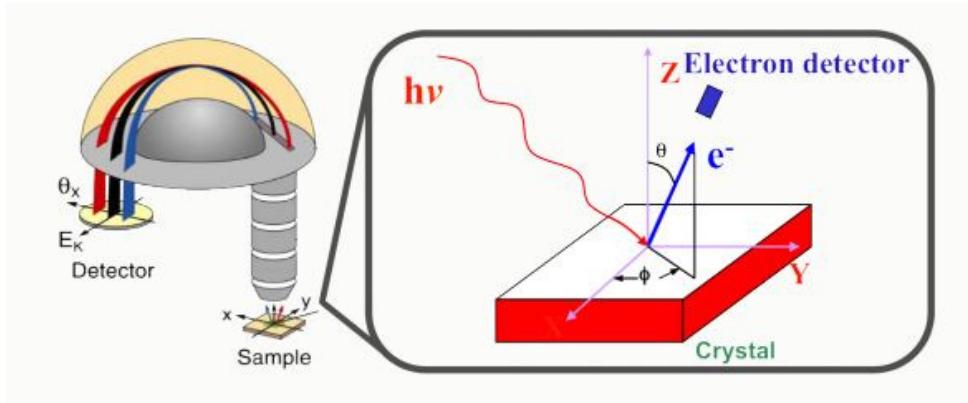
- *Electron-phonon scattering for highly excited electrons*
- *Highly excited electron relaxation in Si*
- *Photoexcited electron relaxation in InSe*

RELAXATION DYNAMICS OF HIGHLY EXCITED ELECTRONS



Main scattering mechanism: intervalley electron-phonon scattering

EXPERIMENTS: ARPES

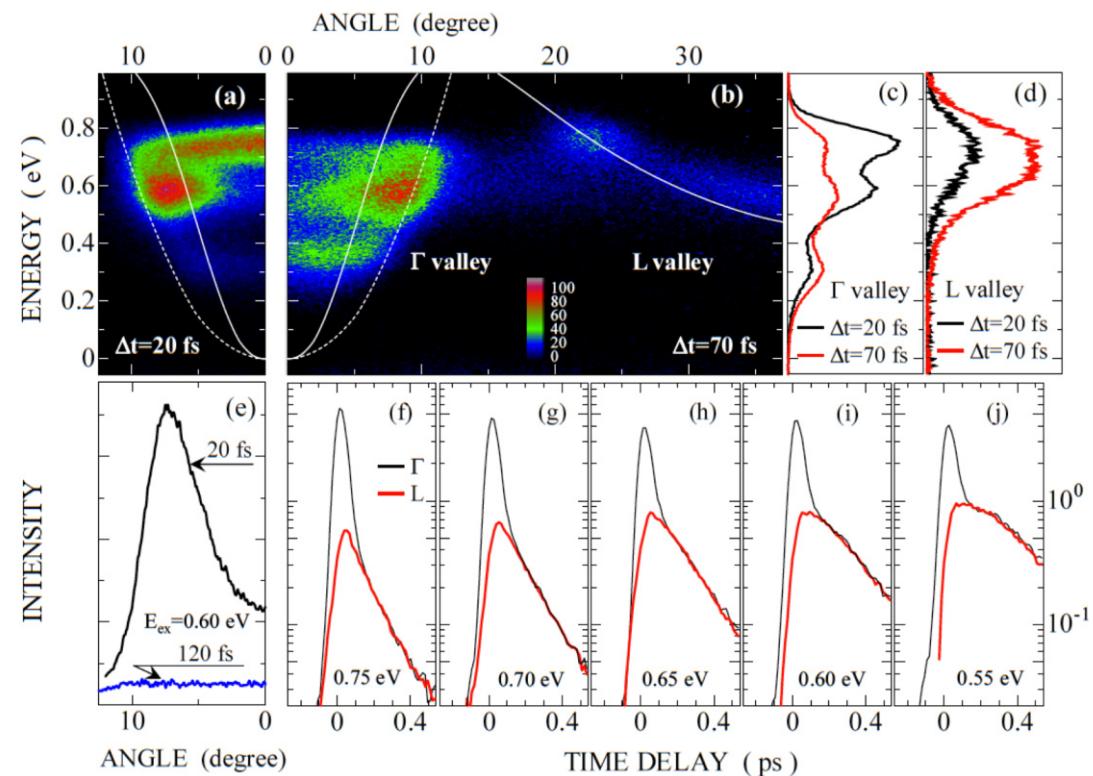


GaAs
300K

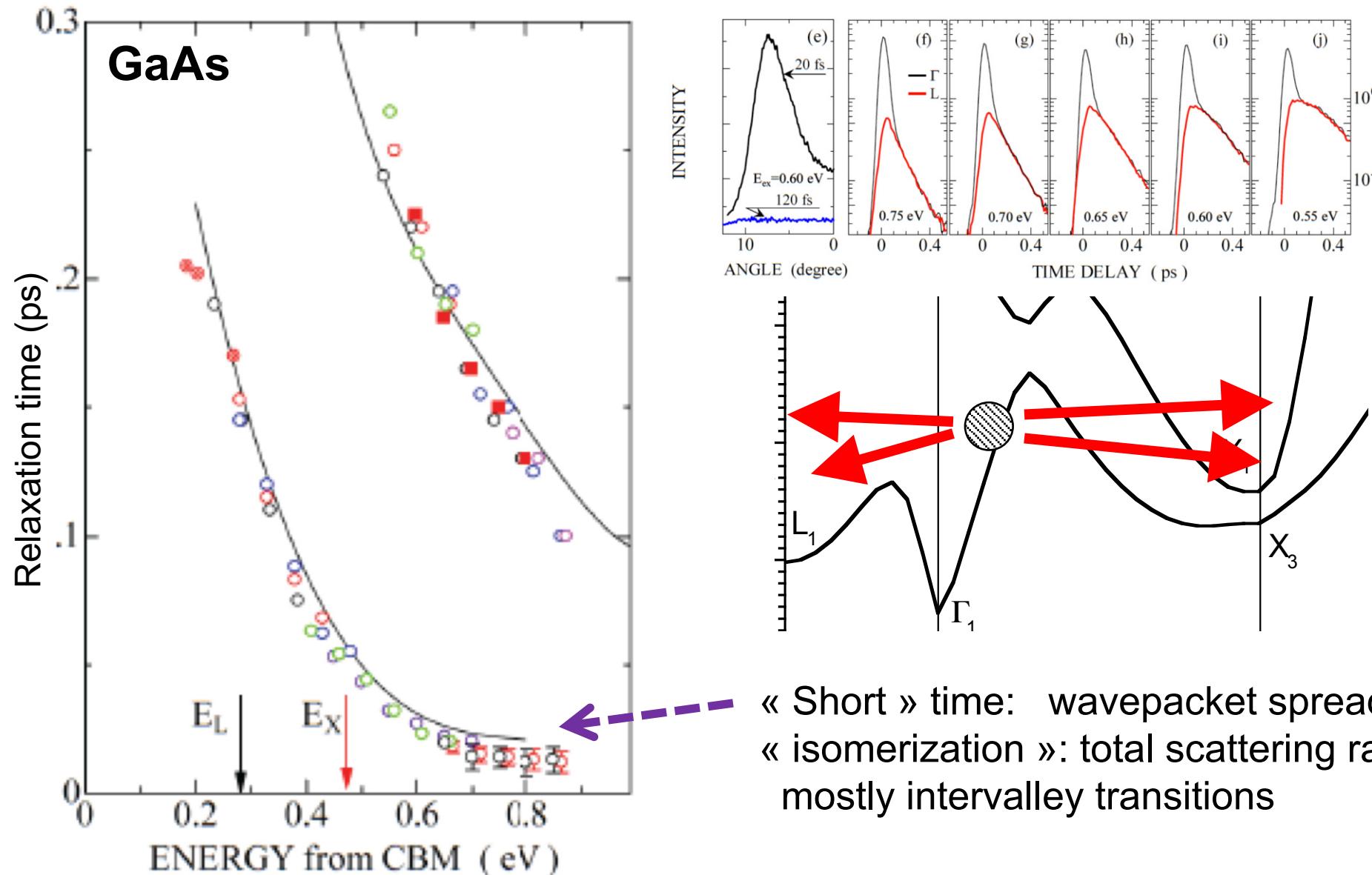
Two distinct relaxation regimes



Pump and probe: 2 laser pulses at different time



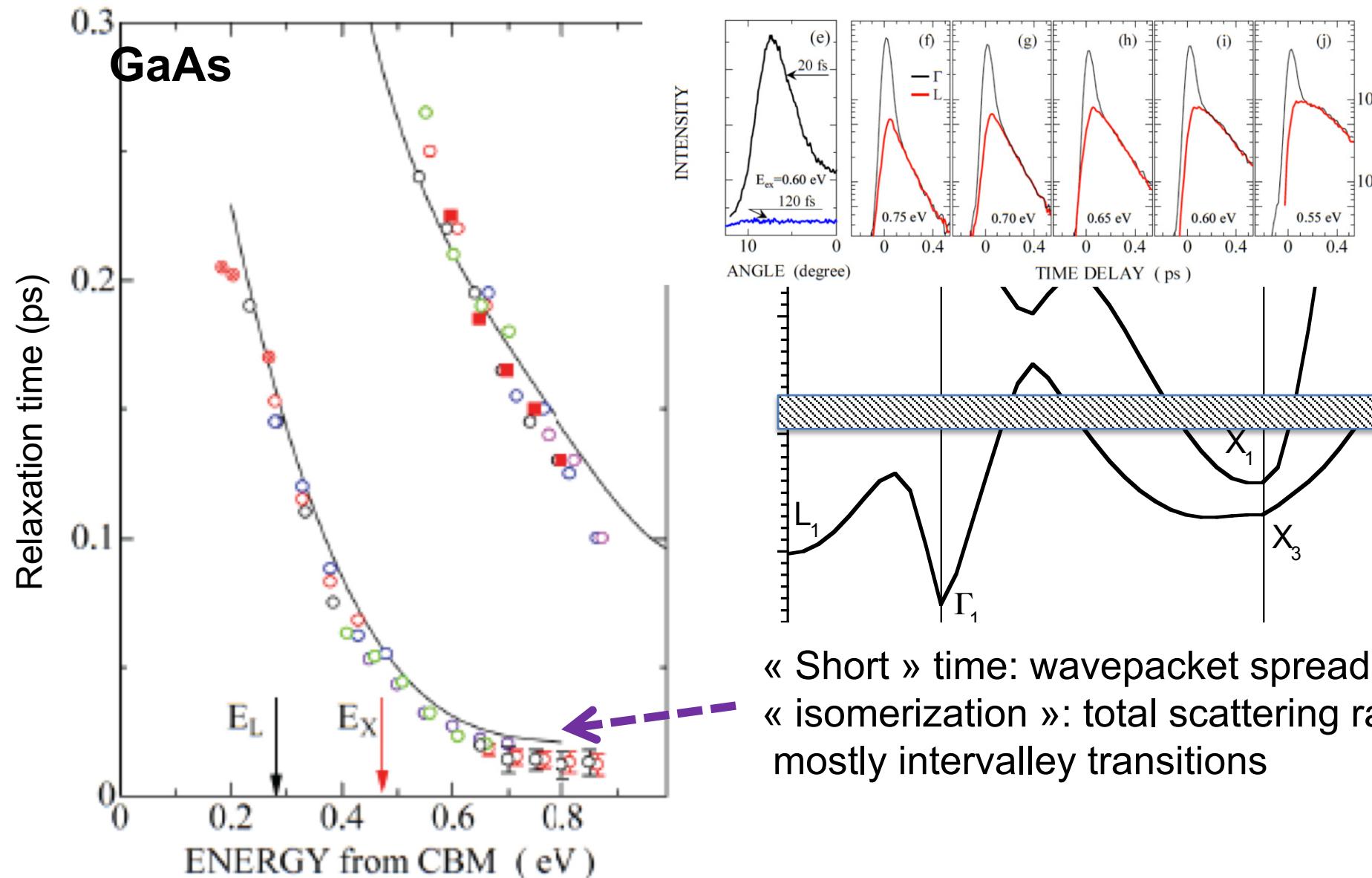
HOT ELECTRON ENSEMBLE (HEE)



Tanimura et al, PRB 93 (2016) 161203 (R).

Sjakste et al, J. Phys: Cond. Mat. 30, 353001 (2018).

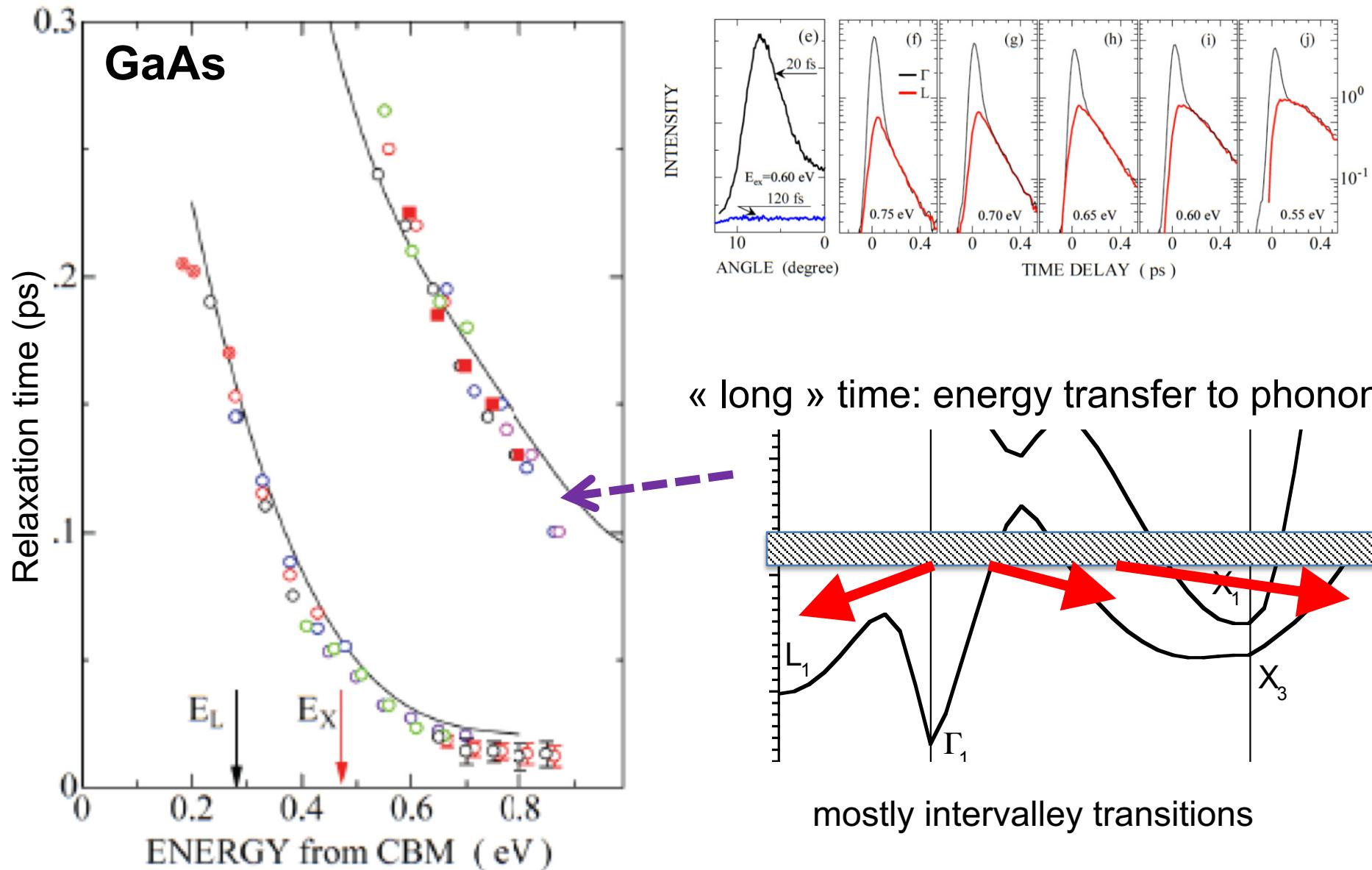
HOT ELECTRON ENSEMBLE (HEE)



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Sjakste et al, J. Phys: Cond. Mat. 30, 353001 (2018).

HOT ELECTRON ENSEMBLE (HEE)



Tanimura, Kanasaki, Tanimura, Sjakste, Vast, Calandra, Mauri, PRB 93 (2016) 161203 (R).

CALCULATIONS: DFPT+Wannier

Reciprocal space
Bloch functions
Initial grid

$$\langle \Psi_{n,k} | \Delta W_q^\lambda | \Psi_{n',k+q} \rangle - \text{Non-local part (if polar)}$$



Real space
Maximally localized Wannier functions
Interpolation on dense grid



Reciprocal space
Bloch functions
Dense grid

$$\langle \Psi_{n,k} | \Delta W_q^\lambda | \Psi_{n',k+q} \rangle + \text{Non-local part (if polar)}$$

J. Sjakste, N. Vast, M. Calandra, F. Mauri, PRB 92 (2015) 054307

C. Verdi, F. Giustino, PRL 115 (2015) 176401



Outline

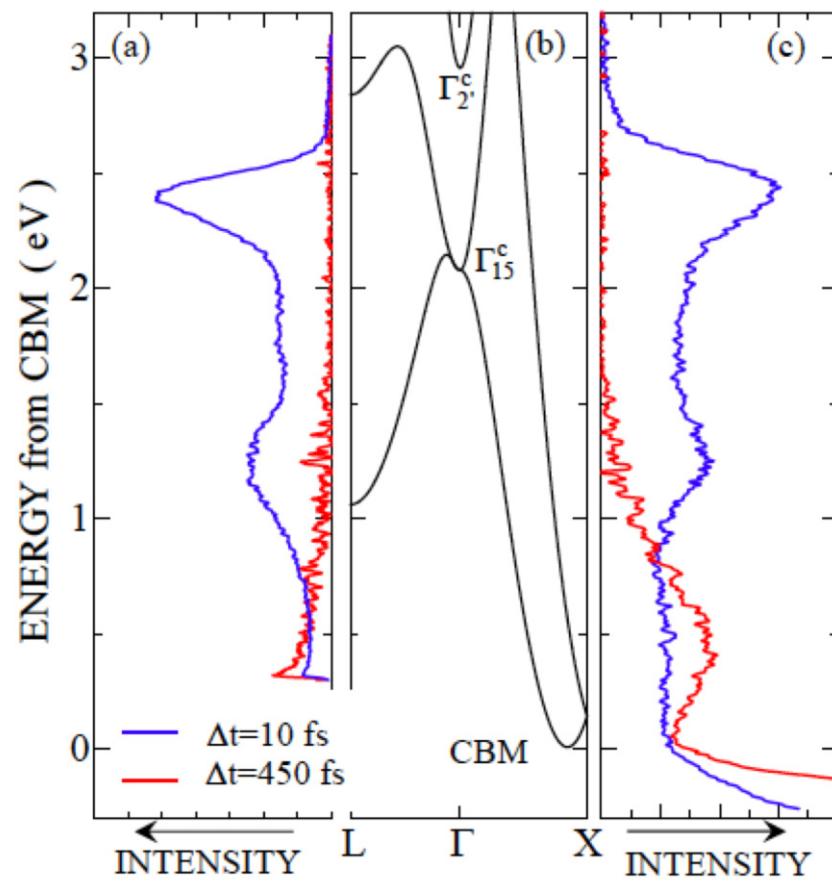
- ***Electron-phonon scattering for highly excited electrons***



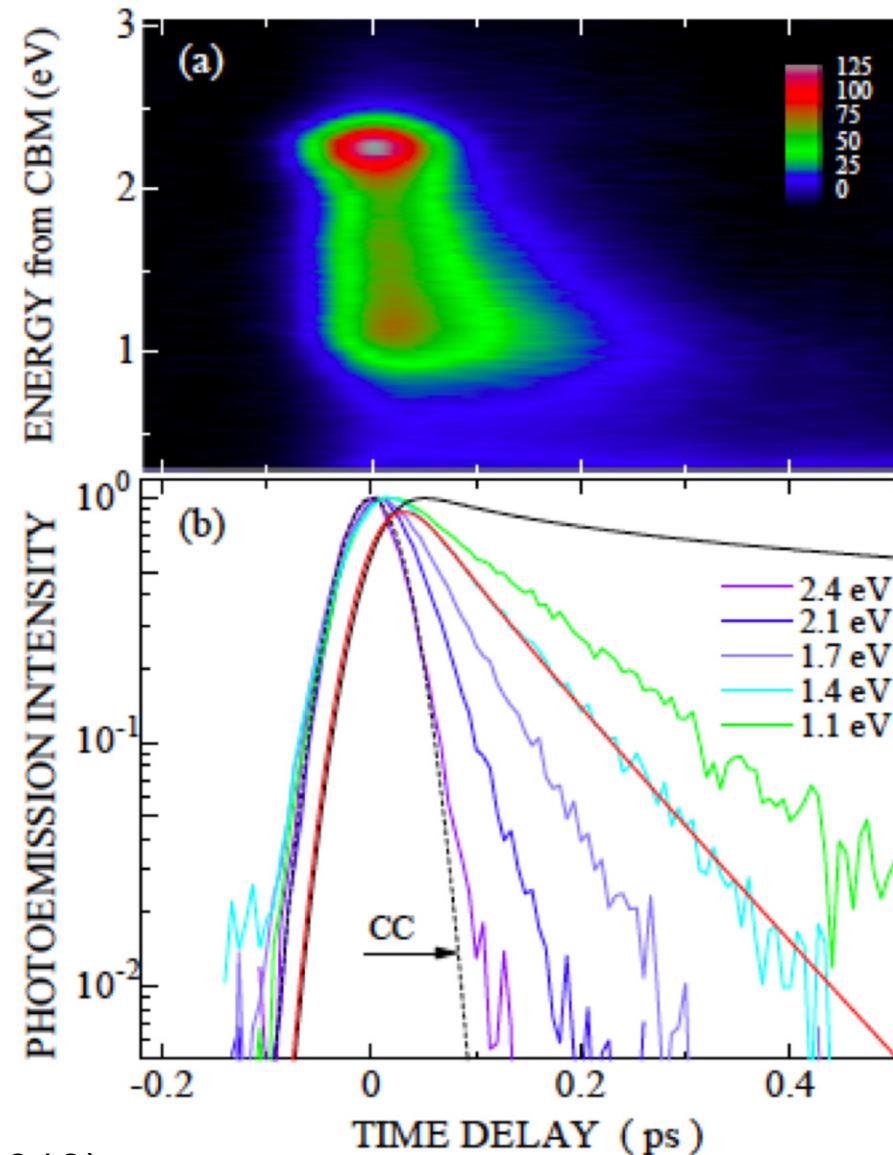
- ***Highly excited electron relaxation in Si***

- ***Photoexcited electron relaxation in InSe***

HIGHLY EXCITED ELECTRONS IN SILICON: 2PPE



Excess energies: 1-3 eV above CBM

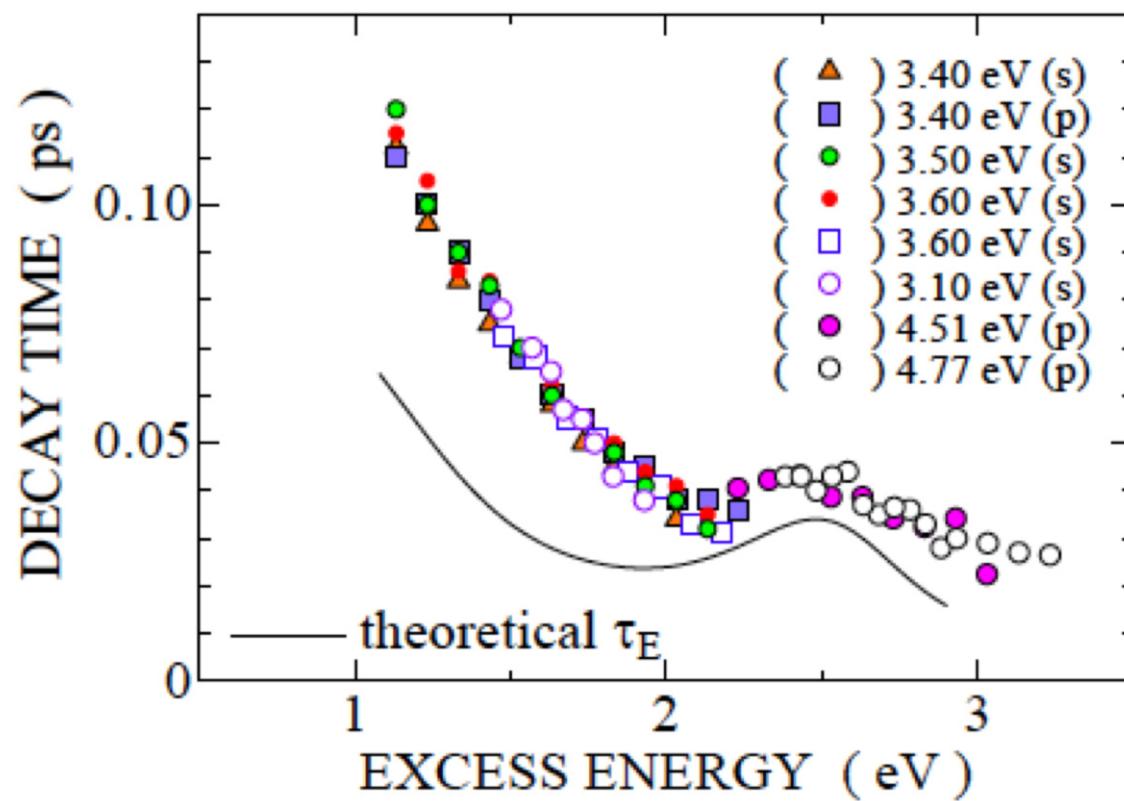


HIGHLY EXCITED ELECTRONS IN SILICON: INTERPRETATION PROBLEM

Previous work: conflict theory/experiment:

Measured relaxation times 10 times longer than calculated ones

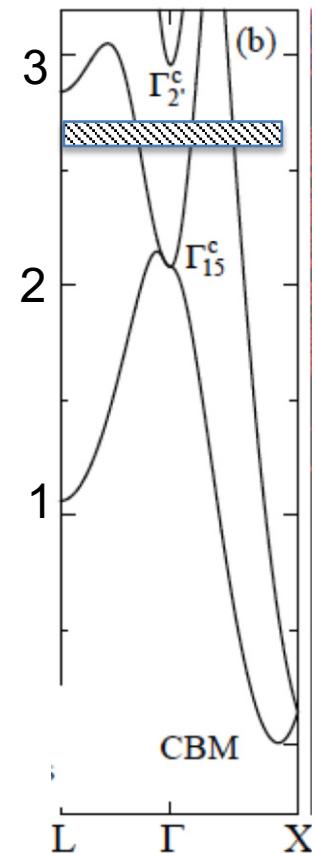
Ichibayashi *et al*, Phys. Rev. B 84, 235210 (2011).



This work: HEE idea

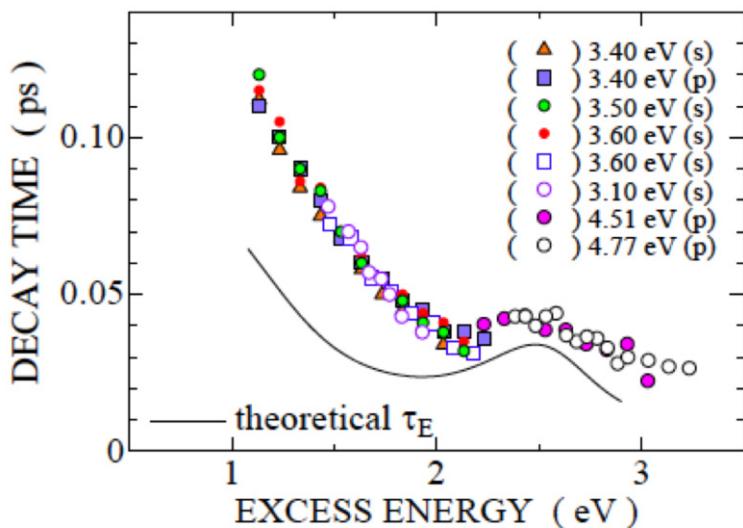
Initial relaxation:
too fast to be measured

Measured relaxation times:
energy loss

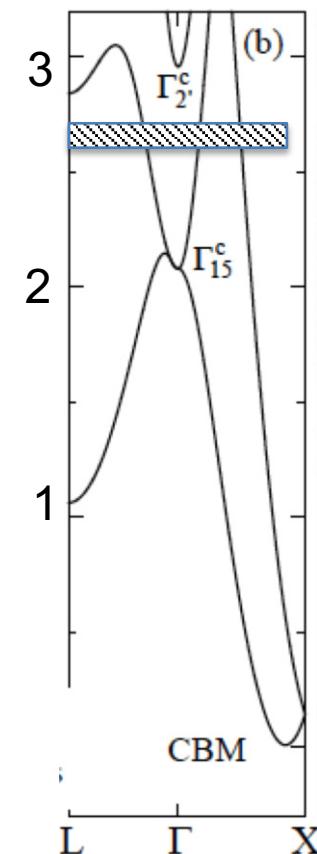
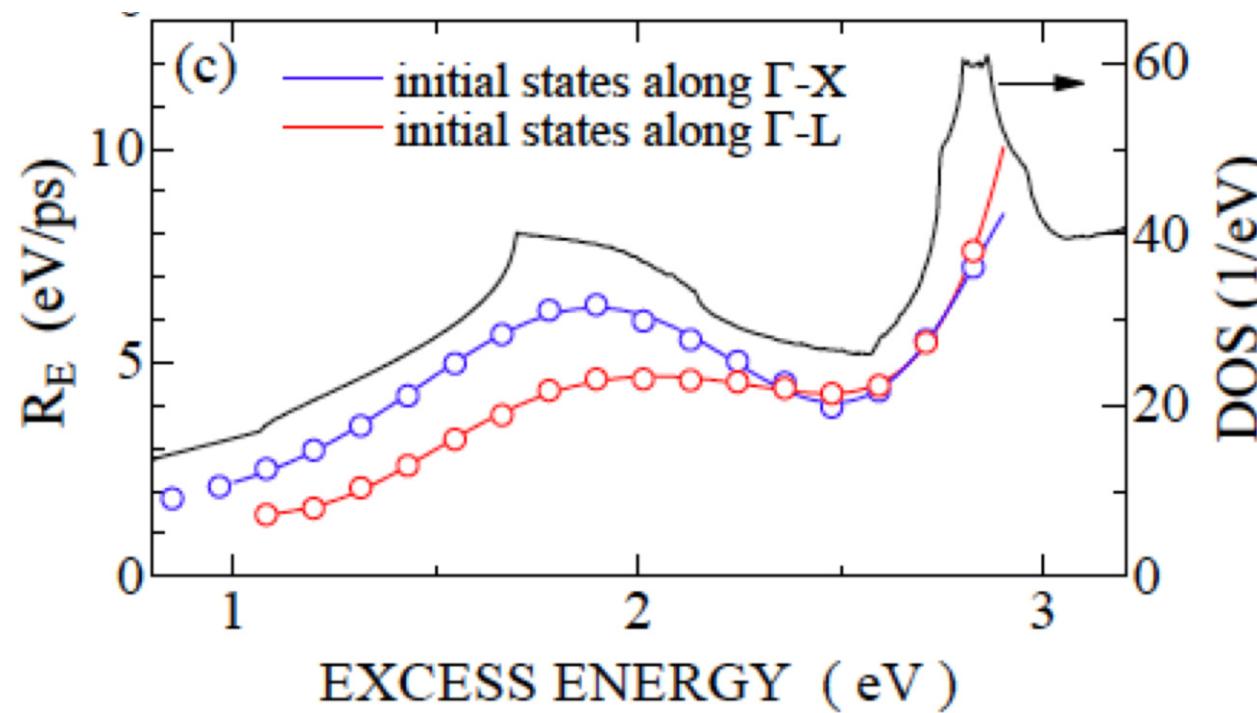


Tanimura, Kanasaki, Tanimura, Sjakste, Vast PRB 100, 03520 (2019).

HIGHLY EXCITED ELECTRONS IN SILICON: ENERGY LOSS RATE



$$dE / \tau_E = \Gamma_{em} \omega_{em} - \Gamma_{abs} \omega_{abs}$$



Energy loss rate:
Determined by DOS of final electronic states

MAIN CHANNELS: IMPORTANT FOR MONTE CARLO

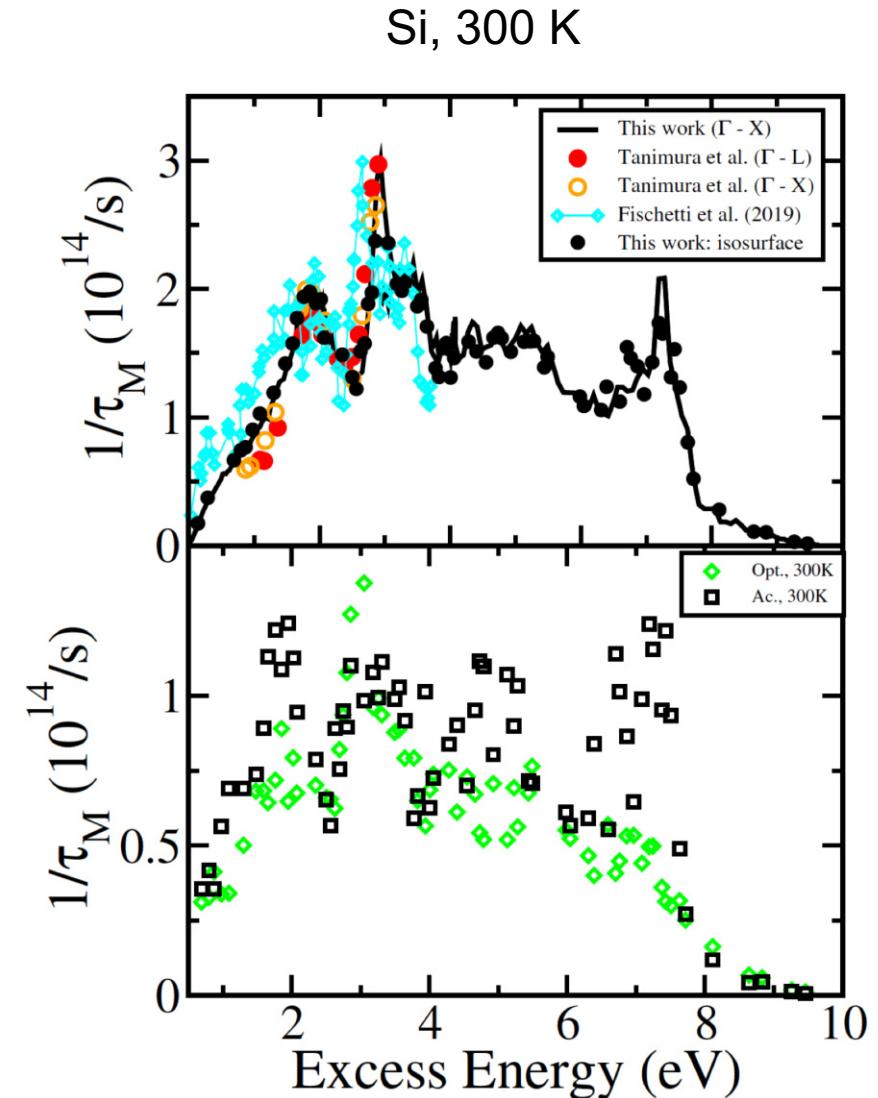


Raja Sen

Total scattering rate:
acoustical phonons are dominant (at 300K)

EPW code, EPIK code: identical results

Also: *Bernardi et al, PRL (2014)*



MAIN CHANNELS: IMPORTANT FOR MONTE CARLO



Raja Sen

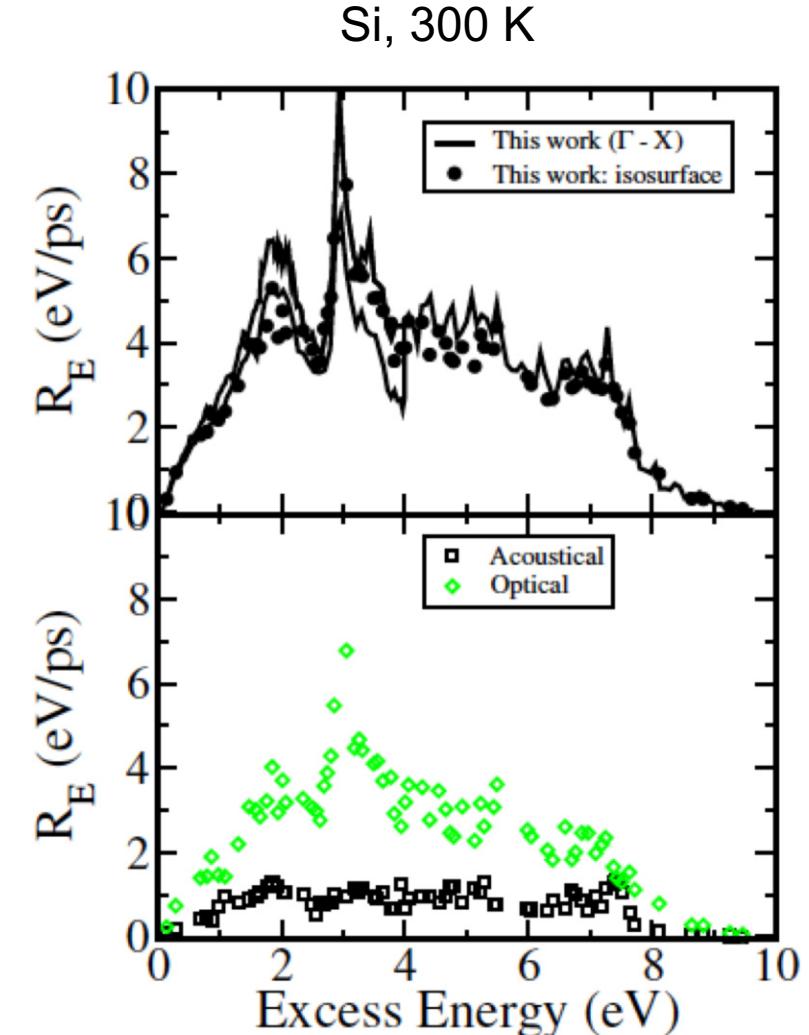
**Energy loss rate:
optical phonons are dominant**

Not unexpected:

Ahmad *et al*, *Phys. Stat. Sol.* 40:631 (1970)

**Temperature-dependent contribution of
acoustical phonons cancels out of energy loss**

EPW code, EPIK code: identical results

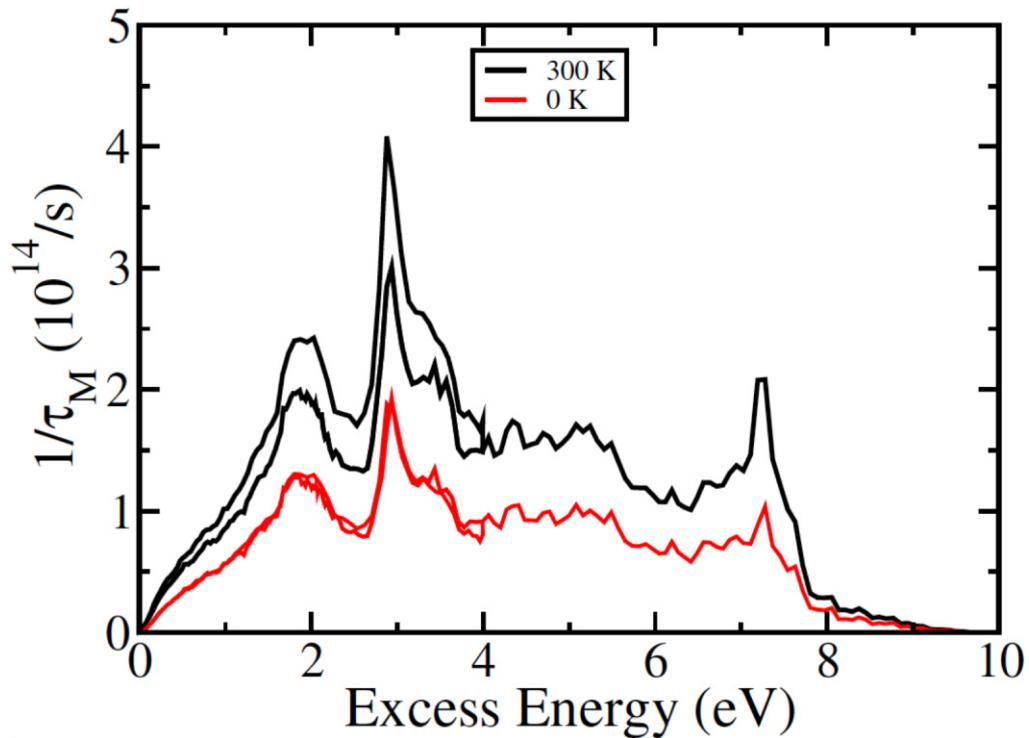


TEMPERATURE DEPENDENCE



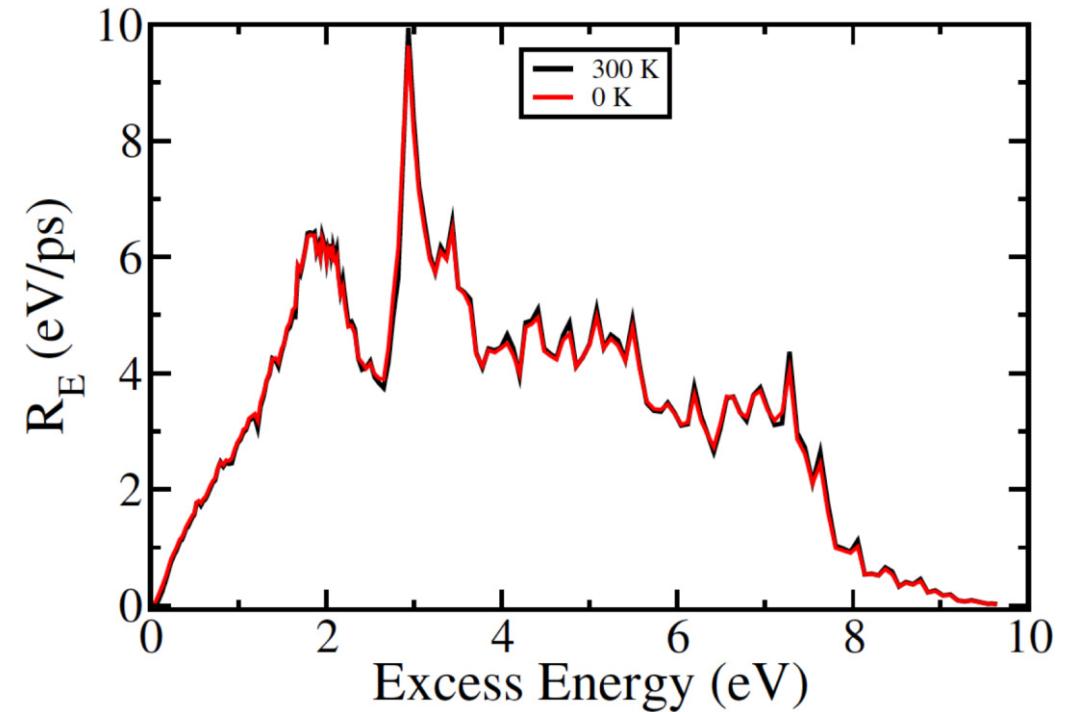
Raja Sen, post-doc

Total scattering rate, Si



Populations of acoustical phonons grow with temperature

Energy loss rate, Si.



Negligible temperature dependence for energy loss rate

Outline

- *Electron-phonon scattering: general picture*
- *Electron-phonon scattering for highly excited electrons*
- *Highly excited electron relaxation in Si*
-  - *Photoexcited electron relaxation in InSe*

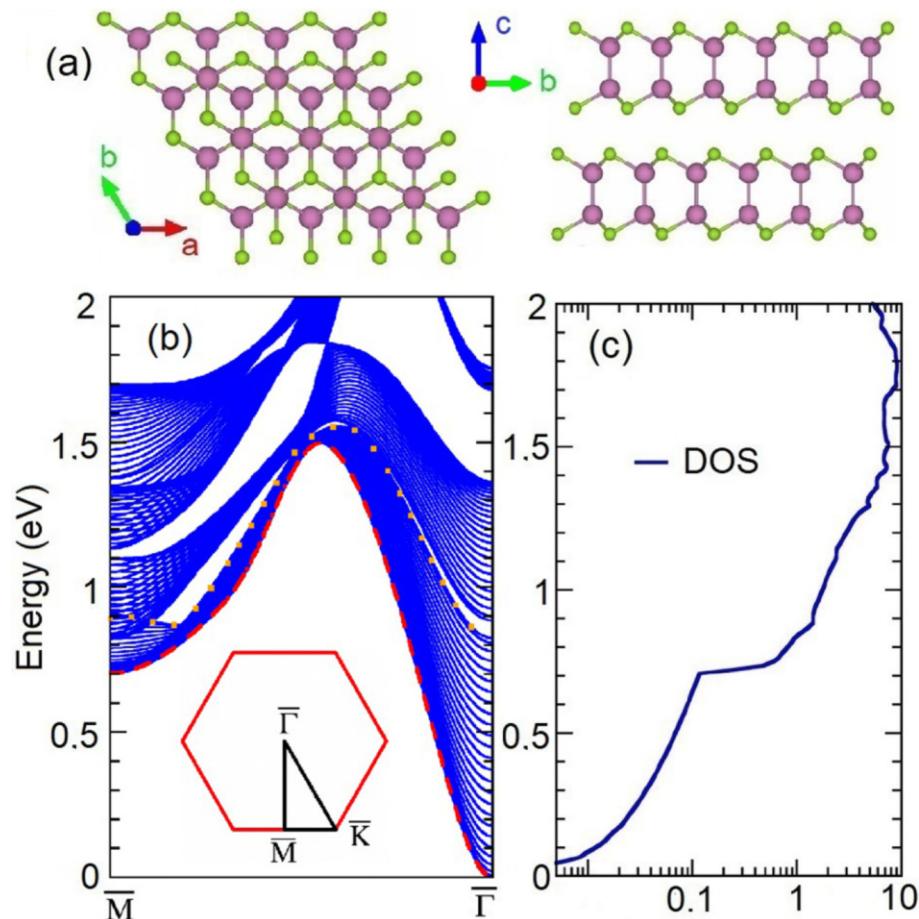
Photoexcited electron relaxation in InSe

Luca PERFETTI
Zhesheng CHEN
Zailan ZHANG
Raphael CABOUAT
Jelena SJAKSTE
Cristine GIORGETTI
Valerie VENIARD
Abdelkarim Ouerghi
Hugo Henck

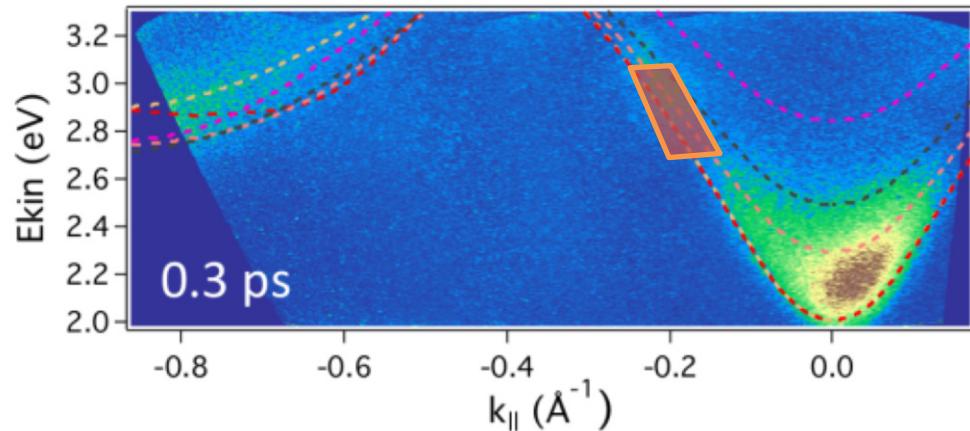
Evangelos PAPALAZAROU
Marino MARSI



- Layered material
- Very narrow Γ valley
- Large M valley

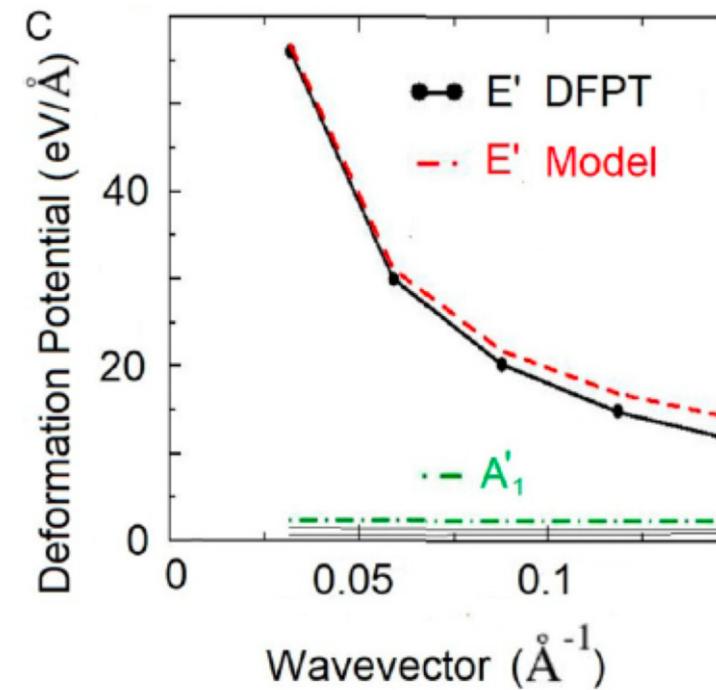


InSe: energy relaxation in Γ valley

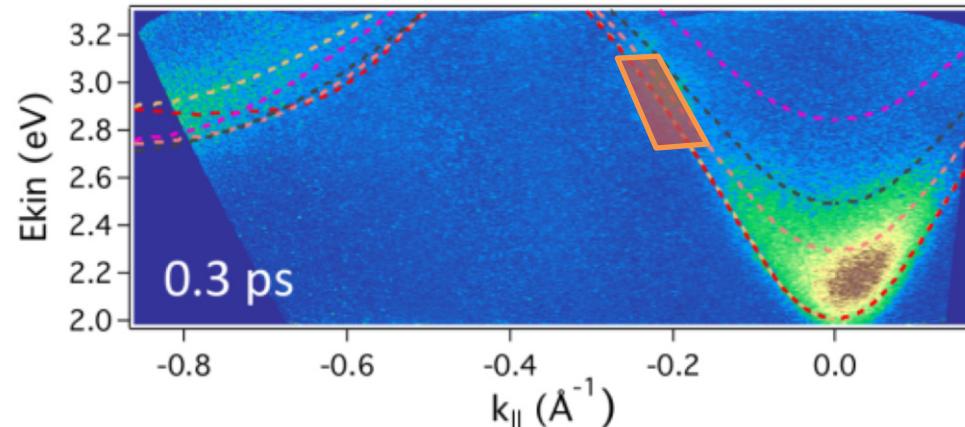


Excess energy below 0.7eV

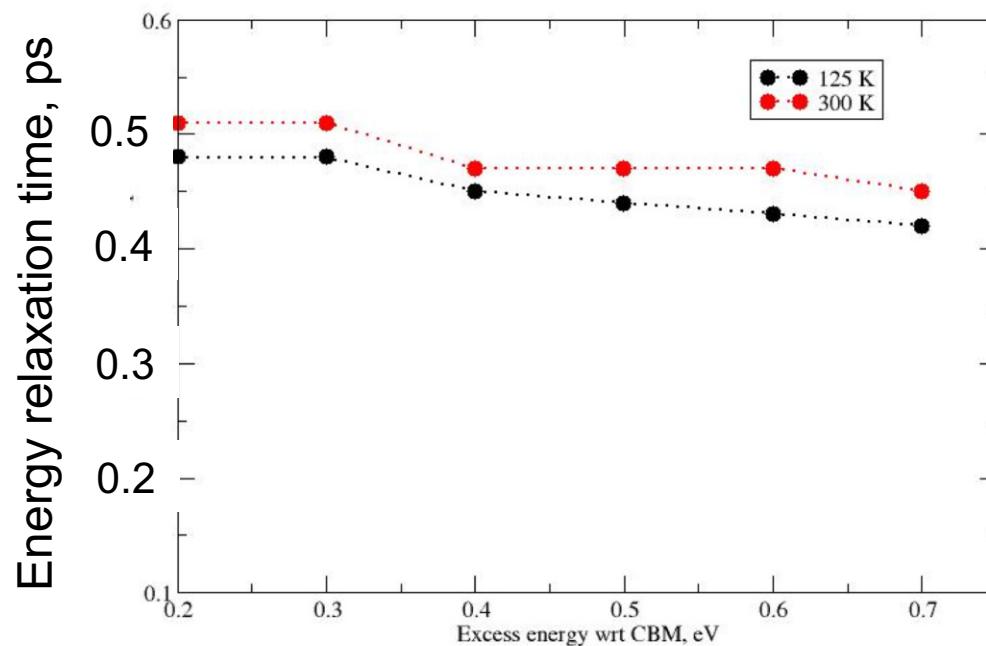
- no intervalley scattering
- very narrow Γ valley ($q < 0.2$ ang.)
- Fröhlich scattering
(scattering by polar phonons)



InSe: energy relaxation in Γ valley

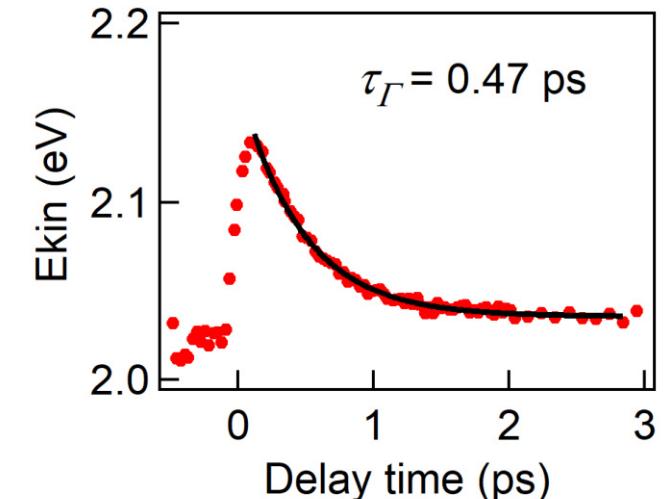


Theory: energy transfer due to coupling with polar phonons



below 0.7 eV

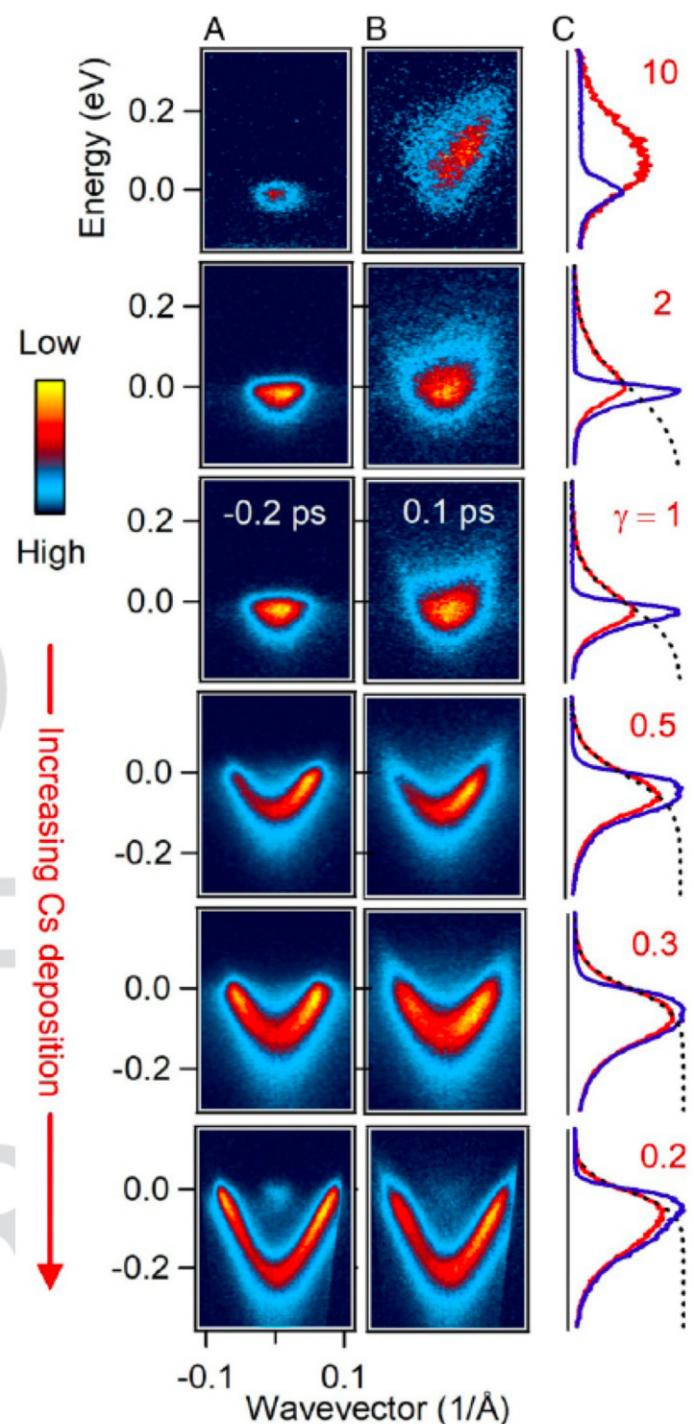
Experiment



scattering by polar phonons

$$\frac{4\pi ie}{\epsilon_{\infty}q^2} q_{\mu} \sum_{\alpha} Z_{\mu\lambda}(\alpha) e_{\lambda}(\alpha\hat{q})$$

Good agreement between theory and experiment.



Quasi-two-dimensional gas on InSe

Experiment:

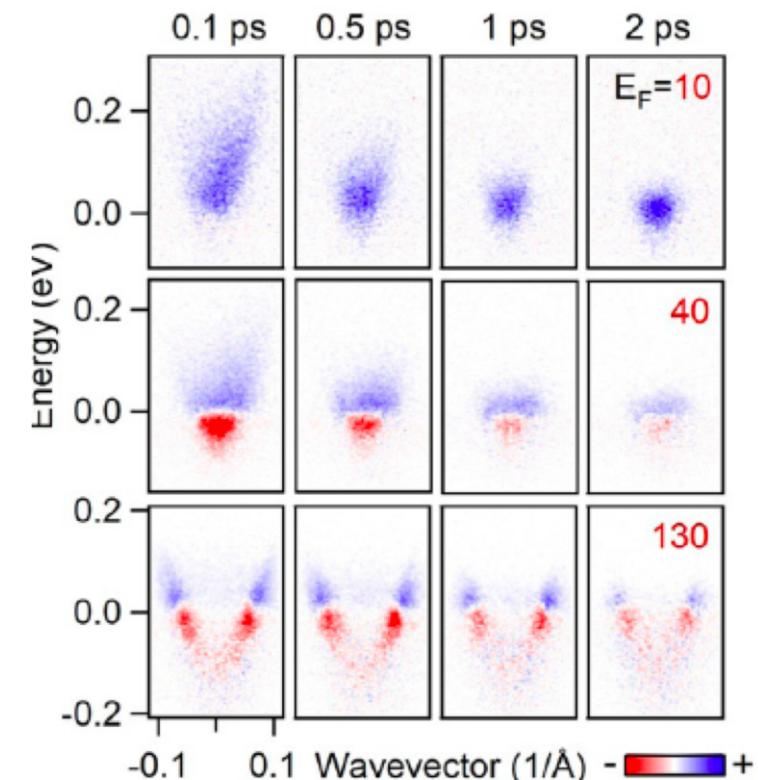
★ Increasing Cs deposition on InSe surface



electron gas created on the surface

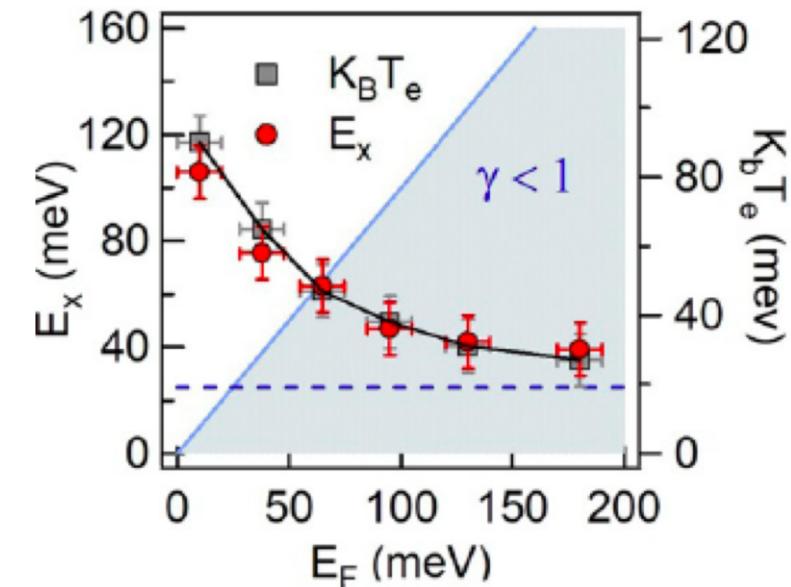
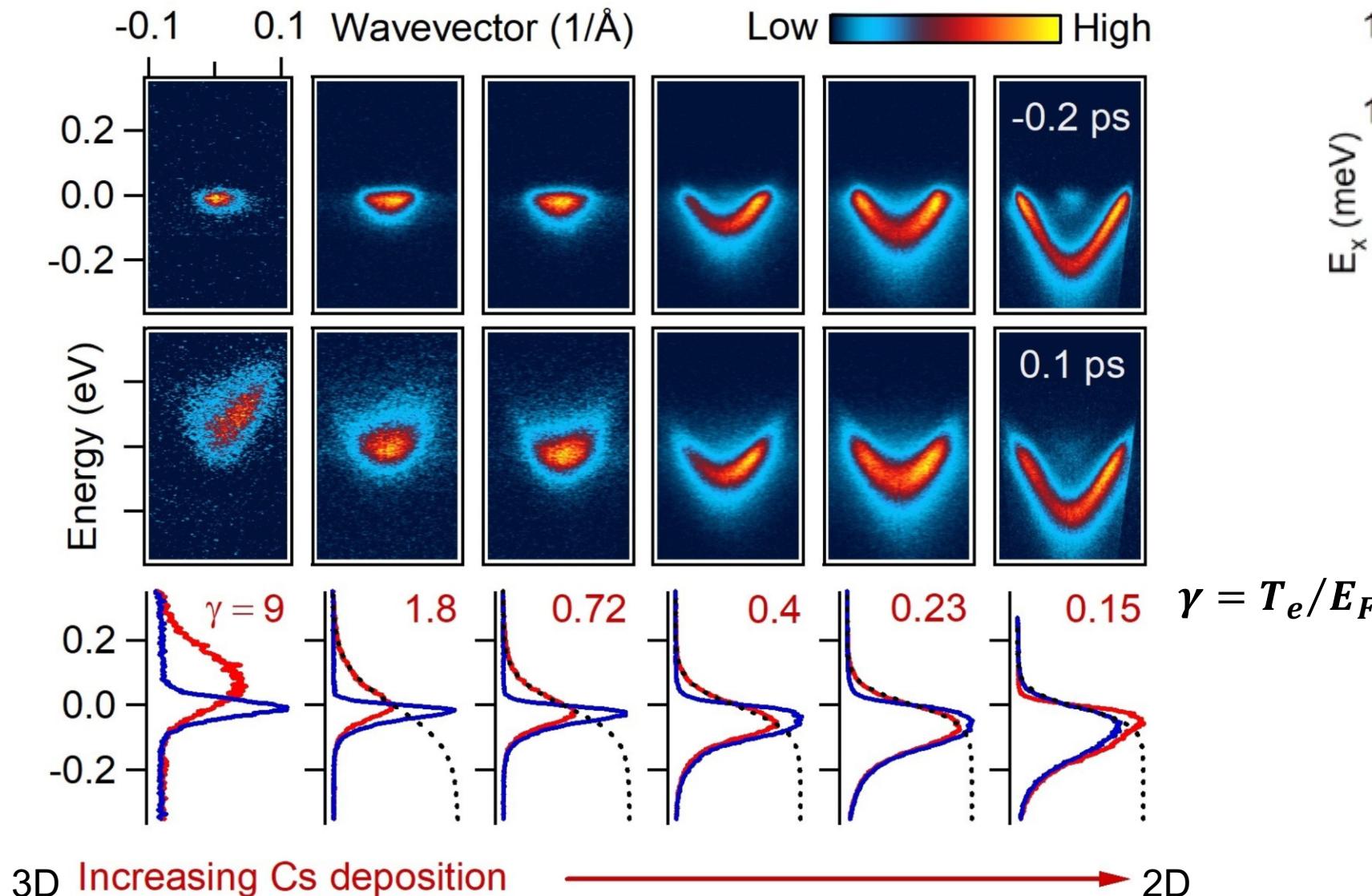
★ Dynamics of excited electrons studied by tr-ARPES

Zhesheng CHEN
Luca PERFETTI



C

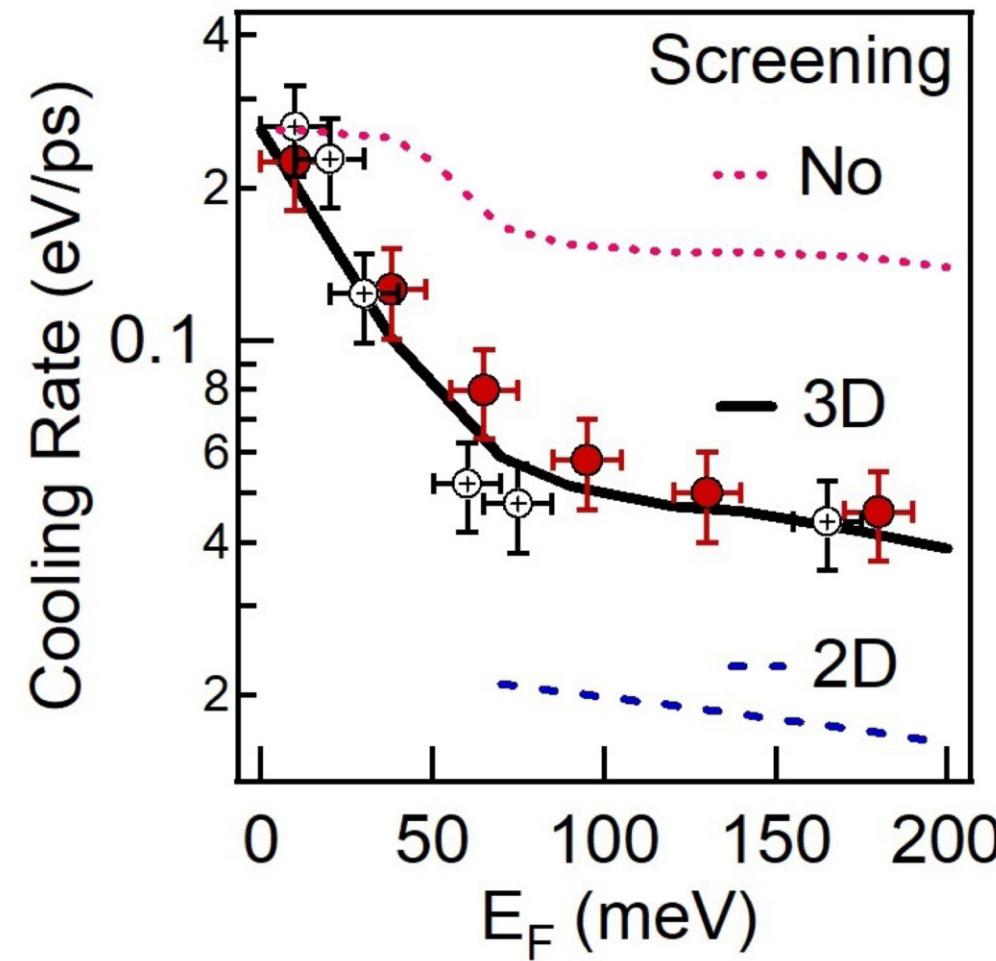
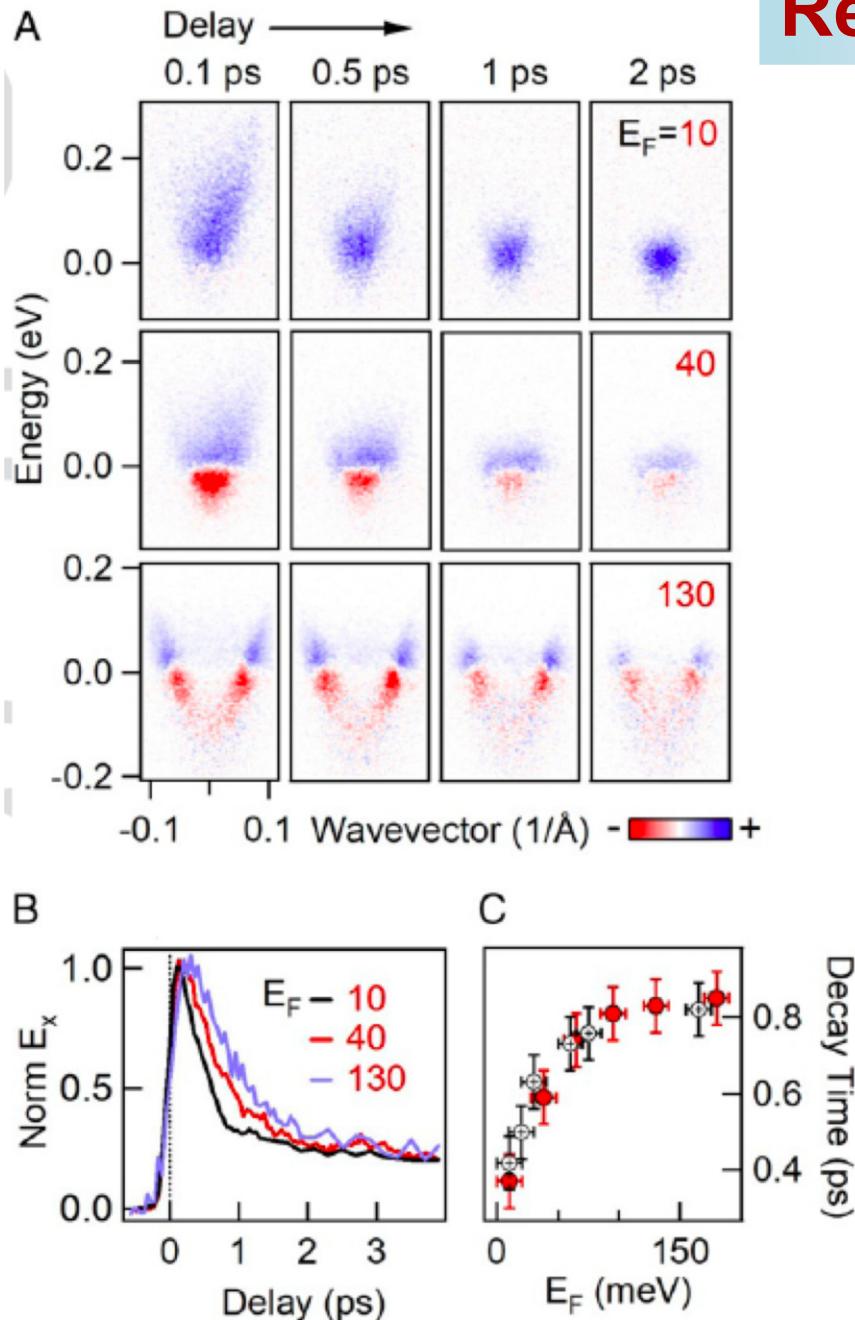
Photoexcited electrons and 2D gas



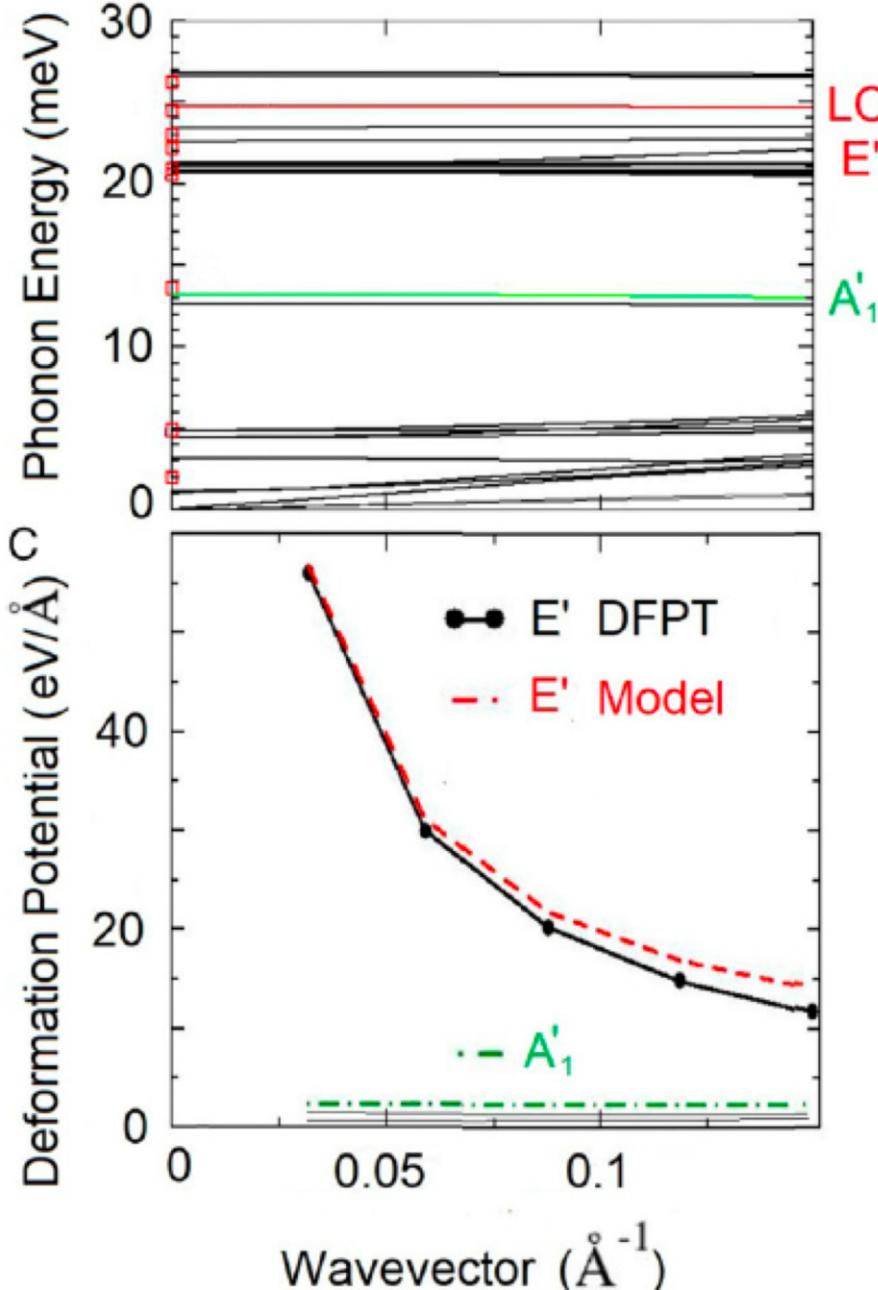
Low deposition:
photoexcited electrons
are non-thermal

High deposition:
photoexcited electrons
are thermalized

Relaxation dynamics of photoexcited electrons



Calculation: screened Fröhlich interaction



3D model:

$$|g_{fr}^{3D}(\mathbf{q})| = \frac{4\pi e^2}{V\epsilon_{bulk}|\mathbf{q}|} \sum_s \sum_{\lambda'} \frac{q_{\lambda'}}{|\mathbf{q}|} Z_{\lambda'\lambda s} \mathbf{e}_{\lambda}^s(\mathbf{q}) / \sqrt{2M_s\omega_q}$$

Vogl, PRB 13 (1976).

3D screening:

$$\epsilon_{bulk}^{scr} = \epsilon_{bulk} \left(1 + \frac{(q_0^{3D})^2}{q^2} \right)$$

Thomas-Fermi

2D model:

$$|g_{fr}^{2D}(\mathbf{q})| = \frac{C_Z}{e_{eff}^0 + r_{eff}|\mathbf{q}_p|}$$

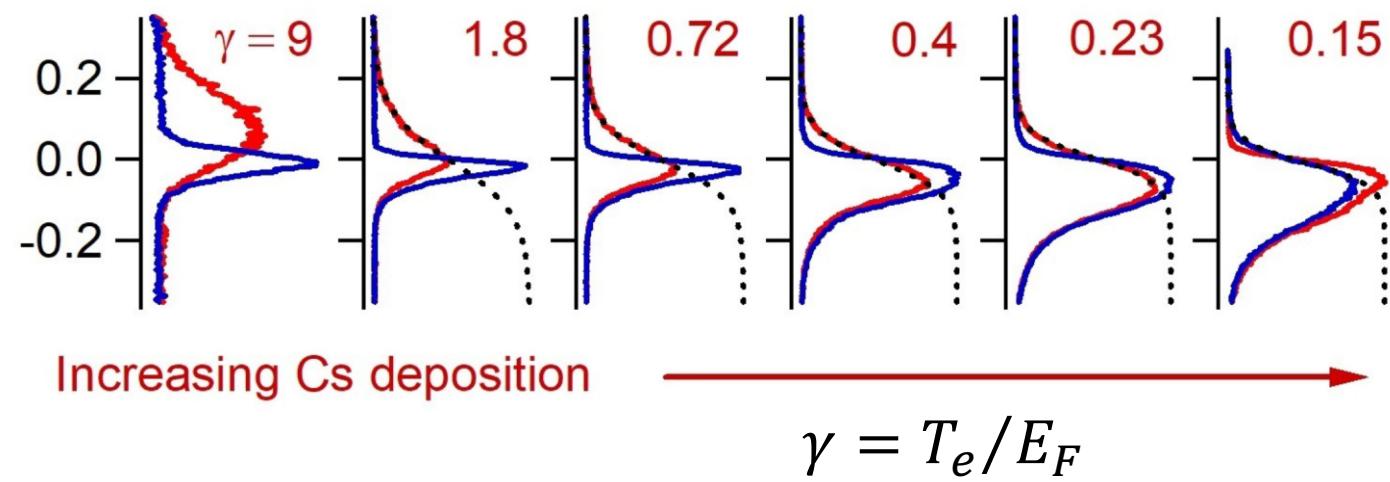
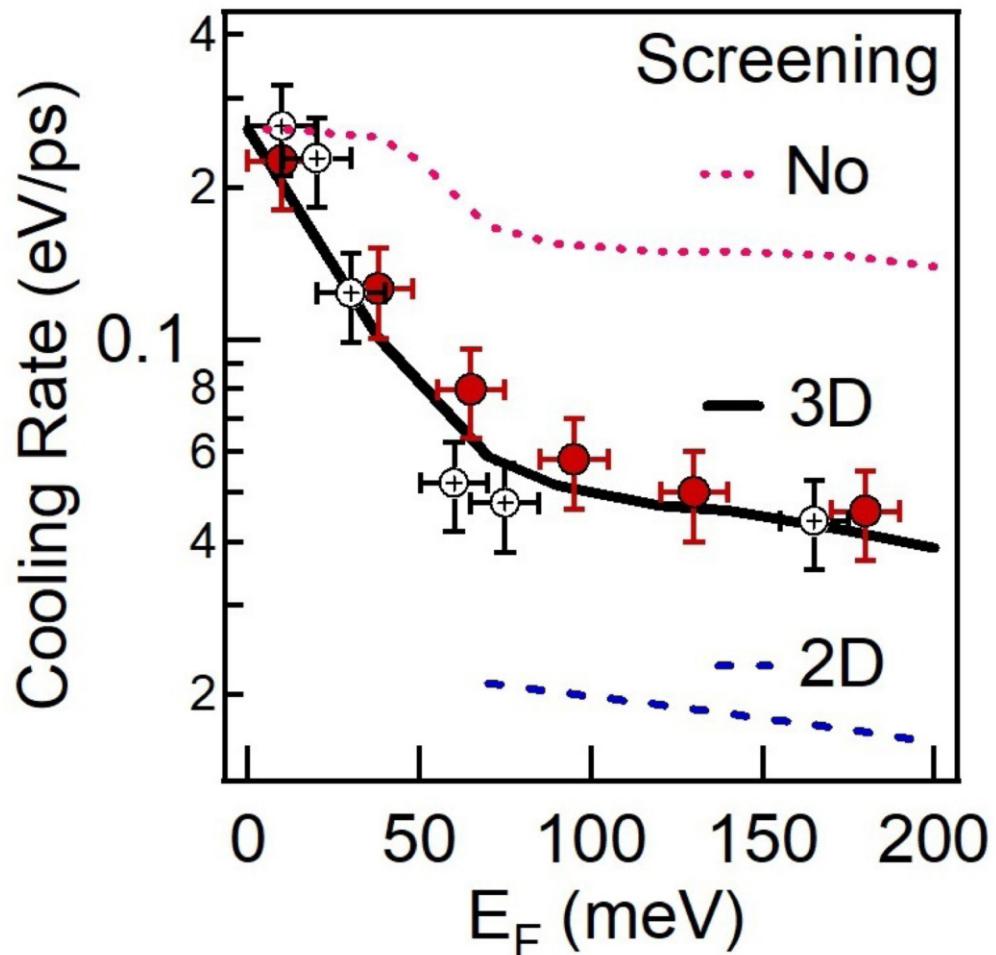
$$C_Z = \frac{2\pi e^2}{A} \times \sum_s \sum_{\lambda'} \frac{q_{\lambda'}}{|\mathbf{q}_p|} Z_{\lambda'\lambda s} \mathbf{e}_{\lambda}^s(\mathbf{q}) / \sqrt{2M_s\omega_q}$$

Sohier, Calandra, Mauri, PRB 94 (2016)

2D screening:

Stern, PRL 18, 546 (1967)

Energy transfer in doped InSe



→ Remote coupling of electrons to 3D phonons

Conclusion

Dynamics of relaxation of highly excited (or « hot »?) electrons in Si and in InSe

- *The concept of hot electron ensemble allowed us to interpret the relaxation times of highly excited electrons in silicon.*
- *In Si, energy loss rate is determined by the DOS of the final electronic states. Negligible temperature dependence.*
- *In InSe, at excess energies below 0.7 eV, energy loss rate is determined by Fröhlich coupling.*
- *Doped InSe:*
 - screening of polar coupling
 - remote coupling to 3D phonons

Thank you for your attention!